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PATENT DATE

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APPLICATION NO.	CONT/PRIOR	CLASS	SUBCLASS	ART UNIT 2/2 EXAMINER
09/864309	F	118/39		JARRETT JARRETT

Shigeyuki Uzawa Izumi Tsukamoto

SSUE CLASSIFICATION

Exposure apparatus, coating/developing system, device manufacturing system. device manufacturing method, semiconductor manufacturing factory, and exposure apparatus maintenance method

ISSUING CLASSIFICATION								
ORIGINAL				CROSS REFERENCE(S)				
ORIGINAL			CLASS SUBCLASS (ONE SUBCLASS PER BLOCK)					
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	DRAWINGS			CLAIMS ALLOWED	
DISCLAIMER	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.
				NOTICE OF ALL	OWANCE MAILED
The term of this patent subsequent to(date) has been disclaimed.	(Assistant	Examiner)	(Date)		
The term of this patent shall not extend beyond the expiration date of U.S Patent. No.	- ¥			ISSUE FEE	
of U.S Patent. No.				Amount Due	Date Paid
	(Primary	Exeminer)	(Date)		TCH NUMBER
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this patent have been disclaimed.	(Legel Instru	nents Examiner)	(Deta)		
WARNING: The information disclosed herein may be n	estricted. Unauthorize	d disclosure mey be	prohibited by the	United States Code Title	35, Sections 122, 181 end 36

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